

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application Serial No. 09/360,292
Filing Date July 22, 1999
Inventor Sujit Sharan et al.
Assignee Micron Technology, Inc.
Group Art Unit 1746
Examiner S. Ahmed
Attorney's Docket No. MI22-1106
Title: Plasma Etching Process (as Amended)



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1-9-2

RESPONSE TO SEPTEMBER 25, 2001 OFFICE ACTION

To: Box Non-Fee Amendment
Assistant Commissioner for Patents
Washington, D.C. 20231

From: Mark S. Matkin (Tel. 509-624-4276; Fax 509-838-3424)
Wells, St. John, Roberts, Gregory & Matkin P.S.
601 West First Avenue, Suite 1300
Spokane, WA 99201-3828

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Sir:

Responsive to the Office Action dated September 25, 2001, Applicant amends and remarks as follows:

AMENDMENTS

In the Title:

Please replace the title with the following: --PLASMA ETCHING PROCESS--.

In the Claims:


Please cancel claims 1-14, 25-34 and 42-60 without prejudice.

REMARKS

The Examiner has required restriction under 35 U.S.C. § 121 between claims 1-14 and 25-34 (Group I - drawn to a process for etching a carbon containing material), claims 15-24 and 35-41 (Group II - drawn to an etching process), claims 42-53 (Group III - drawn to an etching/deposition process), and claims 54-60 (Group IV - drawn to a process of forming a conductive contact). Applicant hereby elects without traverse claims 15-24 and 35-41 (Group II) for prosecution on the merits. Accordingly, claims 1-14, 25-34 and 42-60 (Groups I, III and IV) have been canceled without prejudice.

Respectfully submitted,

Dated: 10-19-01

By: 
Mark S. Matkin
Reg. No. 32,268